

REMARKS/ARGUMENTS

Claims 1, 4, and 7 stand rejected under 35 U.S.C. 102(e) as being anticipated by Ping; claims 5 and 9 stand rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Ping and Ohtani; claims 2 and 6 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Ping and Ohtani as applied to claims 1, 4, 5, 7, and 9, and further in view of Ishihara.

Col. 3, lines 20-35, of the Ping et al. patent discloses forming an amorphous layer 20 using conventional methods such as chemical vapor deposition (col. 3, lines 22-23). After forming the amorphous layer 20, the amorphous layer is exposed to a liquid solution containing one or more fluorine containing species. The Ping et al. patent does not disclose forming the amorphous layer by exposing an upper surface to halogen species. The rejection of claims 1, 4, and 7 under 35 U.S.C. 102(e) as being anticipated by Ping et al. is improper. Claims 1, 4, and 7 are therefore allowable over the cited art.

Claim 5 comprises the limitation of forming an amorphous region in said upper surface by exposing said upper surface to halogen species. As described above this limitation is not described in the Ping et al. patent. This limitation is not found in the Ohtani et al. patent and claim 5 is therefore allowable over the Ping et al. patent in combination with the Ohtani et al. patent. Claim 9 depends on claim 5 and therefore contains the limitations of claim 5. Claim 9 is therefore also allowable over the cited art.

As described above, claims 1, 4, 5, 7 and 9 are allowable over the Ping et al. and the Ohtani et al. patents. Therefore claims 2 and 6 are also allowable over the Ping et al. and the Ohtani et al. patents in further view of the Ishihara et al. patent.

Applicant appreciates the indication that claims 10 and 11 are allowed.

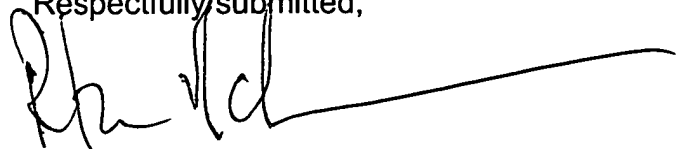
Applicant further appreciates the indication that claims 3 and 8 would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

In light of the above, it is respectfully submitted that the present application is in condition for allowance, and notice to that effect is respectfully requested.

While it is believed that the instant response places the application in condition for allowance, should the Examiner have any further comments or suggestions, it is respectfully requested that the Examiner contact the undersigned in order to expeditiously resolve any outstanding issues.

To the extent necessary, Applicant petitions for an Extension of Time under 37 CFR 1.136. Please charge any fees in connection with the filing of this paper, including extension of time fees, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668.

Respectfully submitted,

A handwritten signature in black ink, appearing to read 'Peter K. McLarty', followed by a long horizontal line extending to the right.

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